

# Features

- Ultrafast body diode
  - Rugged polysilicon gate cell structure
  - Increased Unclamped Inductive Switching (UIS) capability
  - Hermetically sealed, surface mount power package
  - Low package inductance
  - Very low thermal resistance
  - Reverse polarity available upon request

**MSAFX24N50A**

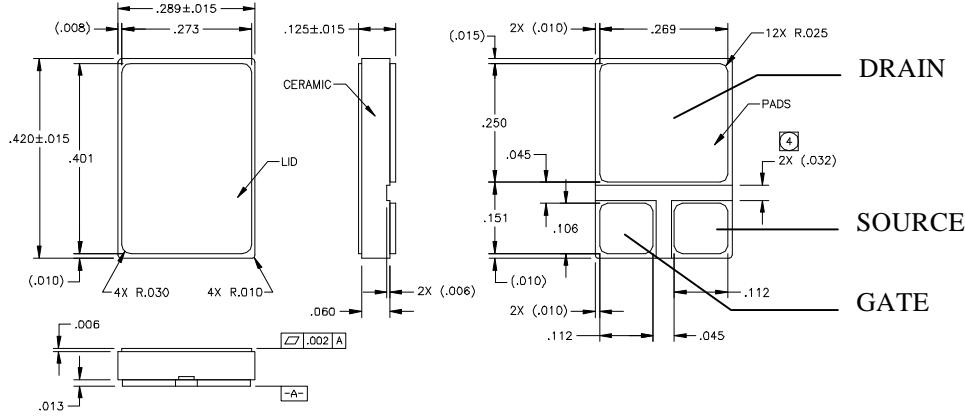
**500 Volts  
24 Amps  
230 mΩ**

**N-CHANNEL  
ENHANCEMENT MODE  
POWER MOSFET**

## **Maximum Ratings @ 25C (unless otherwise specified)**

DESCRIPTION	SYMBOL	MAX.	UNIT
Drain-to-Source Breakdown Voltage (Gate Shorted to Source) @ $T_J \geq 25^\circ\text{C}$	$\text{BV}_{\text{DSS}}$	500	Volts
Drain-to-Gate Breakdown Voltage @ $T_J \geq 25^\circ\text{C}$ , $R_{\text{GS}} = 1 \text{ M}\Omega$	$\text{BV}_{\text{DGR}}$	500	Volts
Continuous Gate-to-Source Voltage	$V_{\text{GS}}$	+/-20	Volts
Transient Gate-to-Source Voltage	$V_{\text{GSM}}$	+/-30	Volts
Continuous Drain Current $T_J = 25^\circ\text{C}$ $T_J = 100^\circ\text{C}$	$I_{\text{D}25}$ $I_{\text{D}100}$	24 20	Amps
Peak Drain Current, pulse width limited by $T_{\text{Jmax}}$	$I_{\text{DM}}$	96	Amps
Repetitive Avalanche Current	$I_{\text{AR}}$	24	Amps
Repetitive Avalanche Energy	$E_{\text{AR}}$	30	mJ
Single Pulse Avalanche Energy	$E_{\text{AS}}$	tbd	mJ
Voltage Rate of Change of the Recovery Diode @ $I_S \leq I_{\text{DM}}$ , $dI/dt \leq 100 \text{ A}/\mu\text{s}$ , $V_{\text{DD}} \leq V_{\text{DSS}}$ , $T_J \leq 150^\circ\text{C}$	$dv/dt$	5.0	V/ns
Power Dissipation	$P_D$	300	Watts
Junction Temperature Range	$T_J$	-55 to +150	°C
Storage Temperature Range	$T_{\text{stg}}$	-55 to +150	°C
Continuous Source Current (Body Diode)	$I_S$	24	Amps
Pulse Source Current (Body Diode)	$I_{\text{SM}}$	96	Amps
Thermal Resistance, Junction to Case	$\theta_{\text{JC}}$	0.25	°C/W

## Mechanical Outline



**MSAFX24N50A****Microsemi**  
Santa Ana, CA  
Progress Powered by Technology**Electrical Parameters @ 25C (unless otherwise specified)**

DESCRIPTION	SYMBOL	CONDITIONS	MIN	TYP.	MAX	UNIT
Drain-to-Source Breakdown Voltage (Gate Shorted to Source)	$BV_{DSS}$	$V_{GS} = 0 \text{ V}, I_D = 250 \mu\text{A}$	500			V
Temperature Coefficient of the Drain-to-Source Breakdown Voltage	$\Delta BV_{DSS}/\Delta T_J$			5.4		V/ $^{\circ}\text{C}$
Gate Threshold Voltage	$V_{GS(\text{th})}$	$V_{DS} = V_{GS}, I_D = 4 \text{ mA}$	2.0		4.0	V
Gate-to-Source Leakage Current	$I_{GSS}$	$V_{GS} = \pm 20V_{DC}, V_{DS} = 0 \text{ V}$ , $T_J = 25^{\circ}\text{C}$ $T_J = 125^{\circ}\text{C}$			$\pm 100$ $\pm 200$	nA
Drain-to-Source Leakage Current (Zero Gate Voltage Drain Current)	$I_{DSs}$	$V_{DS} = 0.8 \cdot BV_{DSS}$ , $T_J = 25^{\circ}\text{C}$ $V_{GS} = 0 \text{ V}$ , $T_J = 125^{\circ}\text{C}$			200 1000	$\mu\text{A}$
Static Drain-to-Source On-State Resistance (1)	$R_{DS(on)}$	$V_{GS} = 10 \text{ V}$ , $I_D = 12 \text{ A}$ , $T_J = 25^{\circ}\text{C}$ $I_D = 24 \text{ A}$ , $T_J = 25^{\circ}\text{C}$ $I_D = 12 \text{ A}$ , $T_J = 125^{\circ}\text{C}$			0.23 0.27	$\Omega$
Forward Transconductance (1)	$g_f$	$V_{DS} \geq 10 \text{ V}; I_D = 24 \text{ A}$	15	21		S
Input Capacitance Output Capacitance Reverse Transfer Capacitance	$C_{iss}$ $C_{oss}$ $C_{rss}$	$V_{GS} = 0 \text{ V}, V_{DS} = 25 \text{ V}, f = 1 \text{ MHz}$		4200 450 135		pF
Turn-on Delay Time Rise Time Turn-off Delay Time Fall Time	$T_{d(on)}$ $t_r$ $t_{d(off)}$ $t_f$	$V_{GS} = 10 \text{ V}, V_{DS} = 250 \text{ V},$ $I_D = 12 \text{ A}, R_G = 2.00 \Omega$		16 33 65 30	25 45 80 40	ns
Total Gate Charge Gate-to-Source Charge Gate-to-Drain (Miller) Charge	$Q_{g(on)}$ $Q_{gs}$ $Q_{gd}$	$V_{GS} = 10 \text{ V}, V_{DS} = 250 \text{ V}, I_D = 12 \text{ A}$		135 30 65	160 40 85	nC
Body Diode Forward Voltage (1)	$V_{SD}$	$I_F = I_S, V_{GS} = 0 \text{ V}$			1.5	V
Reverse Recovery Time (Body Diode)	$t_{rr}$	$I_F = 10 \text{ A}, -di/dt = 100 \text{ A}/\mu\text{s}$ , 25 C 125 C			250 400	ns
Reverse Recovery Charge	$Q_{rr}$	$I_F = 10 \text{ A}, di/dt = 100 \text{ A}/\mu\text{s}$ , 25 C 125 C			1.0 2.0	$\mu\text{C}$

**Notes**

- (1) Pulse test,  $t \leq 300 \mu\text{s}$ , duty cycle  $\delta \leq 2\%$   
(2) Microsemi Corp. does not manufacture the nMOSFET die; contact company for details.